

W1.1 Image Quality of Printers

INCITS W1.1 2005-009

Gloss and Gloss Uniformity

Yee Ng, Feb 18, 2005

Gloss/Gloss Uniformity Ad Hoc Teleconference Meeting Notes:

(2/22/2005 teleconferences)

Present: Yee Ng (Chair, NexPress), Eric Maggard (HP), C. K. Kuo (Nexpress)

Absent members:

Mike Pointer (National Physical Lab, UK), Pashant Mehta (ImageExpert), John Kessler (Paxar), Sanjay Monie (W.R. Grace), Michael Viola (Cabot Corp), Eric Zeise (Nexpress), Frans Gaykema (Oce, Netherland), Tetsuya Itoh (KonicaMinolta, Japan), Luke Cui (Lexmark), Dale Mashtare (Xerox), Ming-Kai Tse (QEA), Tom Graczyk (Arkwright), Peter Morris (HP)

Next Teleconference: Tuesday, March 8, 2005 @ 1:30 EST.

Agenda:

- (1) ISO CD 19799 – answer to questions from country vote
- (2) ISO 19751 – gloss uniformity path forward discussion.

The gloss uniformity ad hoc team met on 2/22/2005 and approved the agenda. YN briefed the team on the follow-through action with respect to ISO CD 19799 – country vote. In relationship to the comment from Philippines on engine environment, the current office environment (temperature, humidity) is supposed to be for an office with air-conditioning. However one will need to go back and examine the environmental condition of the Standard and see whether it needs to be modified for higher temperature/humidity office environment. In relationship to the 3 comments from JP, the team discusses them and here are the action items:

- (1) In relationship to the G60/G75 switch over point, our proposal is still using the average gloss value of the 40 steps differential gloss test chart using G60 measurement to determine the switch-over point. After that the differential gloss data is reported in the chosen gloss value (not a mixture of two gloss angle measurement). We will re-examine the measured data for the JP and US samples to see whether the G60 average of 15 is still a reasonable switch-over point.
- (2) JP have problem understanding the experiment that lead to the differential gloss visual scale. Also there are concerned that the gloss values appears to be bimodal in some cases. CK will try to explain the procedure that lead to the experiment. Also a bimodal distribution in gloss for samples that have lots of differential gloss is normal. A more Gaussian distribution with small sigma typically signifies low differential gloss. So the test chart is doing what it is supposed to be doing to

discover the issue. Whether one will agreed to do an International round-robin subjective evaluation experiment or not is not clear. However this step will have to be done for ISO 19751 anyway, so one might as well do it now.

- (3) JP is concerned there are too many patches (40) to measure for the differential gloss test chart and wants to know why. CK and YN will go back to the original support vector stuff to find out ~ how many patches are considered reasonable for the test and get back to JP.

The team further discusses the steps that one need to do to move ISO 19751-2 forward. The first step is relating to the differential gloss jnd which coincide with the ISO 19799 issue above. The second item relates to the gloss artifact issue that YN will contact DM to discuss.

Next call-in conference: Tuesday, Feb 22, 2005, 1:30PM EST.

Proposed agenda:

- (1) ISO 19799 response to JP discussion
- (2) Discussion on ISO/IEC WD 19751-2 relating to how to get JND for Differential Gloss and Gloss Artifact
- (3) Follow through with DOI.

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